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THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the application of:
HUI-JUNG WU, ET AL.

Docket: 30-4731 (4780) DIV-1

Serial Number: 09/841,453

Group Art Unit: 2829

Filed: April 24, 2001

Examiner: Asok K. Sarkar

For: USE OF MULTIFUNCTIONAL SI-BASED OLIGOMER/POLYMER FOR THE
SURFACE MODIFICATION OF NANOPOROUS SILICA FILMS

AMENDMENT

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In response to the Office Action mailed April 23, 2003, please amend the above
identified patent application as follows:

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CLAIM AMENDMENTS

1. (Previously Cancelled).
2. (Previously Amended) The nanoporous silica film of claim 20 wherein said reaction is conducted in the presence of at least one solvent or co-solvent.
3. (Previously Amended) The nanoporous silica film of claim 20, said silica having a pore structure that comprises silanols, and wherein said reaction is conducted for a period of time sufficient for said surface modification agent to produce a treated nanoporous silica film having a dielectric constant of about 3 or less.